

Co-Cr-Pt-B FERROMAGNETIC SPUTTERING TARGET

ABSTRACT

Provided is a Co-Cr-Pt-B ferromagnetic sputtering target including: a Co-Cr-Pt-B alloy phase (A) containing more than 0% by atom and 30% by atom or less of B, in which B is distributed throughout without B agglomerate phases unevenly distributed; an alloy phase (B) which is any one of a Co-B alloy, a Co-Cr-B alloy, or a Co-Pt-B alloy, containing more than 0% by atom and 20% by atom or less of B, in which B is distributed throughout without B agglomerate phases unevenly distributed; wherein the alloy phase (A) accounts for 50% by volume or more in the sputtering target; and wherein the alloy phase (B) accounts for less than 50% by volume in the sputtering target.